

## AMENDMENTS TO THE CLAIMS

**1. (Currently Amended)** A chemical-amplification positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) a polyhydroxystyrene-based resinous ingredient of which the hydroxyl groups are partly substituted by acid-dissociable substituent groups capable of being dissociated by interacting with an acid; and

(B) a radiation-sensitive acid-generating compound capable of releasing an acid by irradiation, said acid-generating agent being selected from the group consisting of diazomethane compounds and onium salt compounds of which the anionic counterpart is a C<sub>1</sub>-C<sub>15</sub> halogenoalkylsulfonate anion,

the resinous ingredient as the component (A) being a combination comprising (A1) a first polyhydroxystyrene resin substituted for from 30 to 60% of the hydroxyl groups by tert-butoxycarbonyl groups and (A2) a second polyhydroxystyrene resin substituted for from 5 to 20% of the hydroxyl groups by tert-butoxycarbonyl groups which are the same as in the first polyhydroxystyrene resin (A1), wherein the ratio of the maximum weight-average molecular weight  $Mw_{max}$  to the minimum weight-average molecular weight  $Mw_{min}$  in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than ~~1.5~~ 1.3, and the weight proportion of said first and second polyhydroxystyrene resins (A1) to (A2) is in the range of 1:9 to 9:1, and

(C) an amine compound.

### **2-6. (Canceled)**

**7. (Previously presented)** The chemical-amplification positive-working photoresist composition as claimed in claim ~~[[5]]~~ 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of (A1) a first polyhydroxystyrene resin substituted for from 35 to 60% of the hydroxyl groups by the acid-dissociable substituent groups

and (A2) a second polyhydroxystyrene resin substituted for from 5 to 15% of the hydroxyl groups by the acid-dissociable substituent groups.

**8. (Original)** The chemical-amplification positive-working photoresist composition as claimed in claim 7 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of the first and second polyhydroxystyrene resins (A1) and (A2) in a weight proportion in the range from 4:6 to 1:9.

**9-10. (Canceled)**